## WHAT IS CLAIMED IS:

- 1. A semiconductor device comprising:
- a crystalline semiconductor film having a thickness between 5 and 40 nm, wherein:
- a carbon concentration and a nitrogen concentration are  $5 \times 10^{18}$  atoms/cm<sup>3</sup> or less, and an oxygen concentration is  $1.5 \times 10^{19}$  atoms/cm<sup>3</sup> or less;

a main orientation plane is a {110} plane;

an absolute value of a rotation angle made by equivalent axes between adjacent crystal grains or by axes in rotation relation of 70.5° with respect to the equivalent axes is within 4°.

- 2. A semiconductor device according to claim 1, wherein the crystalline semiconductor film is a single crystal or substantially a single crystal.
- 3. A semiconductor device according to claim 1, wherein the crystalline semiconductor film comprises  $Si_xGe_{(1-x)}$  (0<x<1).
- 4. A semiconductor device according to claim 1, wherein the semiconductor device is at least one of a liquid crystal display device and an EL display device.
- 5. A semiconductor device according to claim 1, wherein the semiconductor device is at least one selected from the group consisting of a personal computer, a video camera, a goggle-type display, a digital camera, a player using a recording medium, a mobile computer, and a projector.
  - 6. A semiconductor device comprising:
- a crystalline semiconductor film having a thickness between 5 and 40 nm, wherein:
  - a carbon concentration and a nitrogen concentration are 1  $\times$   $10^{18}$

atoms/cm³ or less, and an oxygen concentration is 5 x 10<sup>18</sup> atoms/cm³ or less; a main orientation plane is a {110} plane;

an absolute value of a rotation angle made by equivalent axes between adjacent crystal grains or by axes in rotation relation of 70.5° with respect to the equivalent axes is within 4°.

- 7. A semiconductor device according to claim 6, wherein the crystalline semiconductor film is a single crystal or substantially a single crystal.
- 8. A semiconductor device according to claim 6, wherein the crystalline semiconductor film comprises  $Si_xGe_{(1-x)}$  (0<x<1).
- 9. A semiconductor device according to claim 6, wherein the semiconductor device is at least one of a liquid crystal display device and an EL display device.
- 10. A semiconductor device according to claim 6, wherein the semiconductor device is at least one selected from the group consisting of a personal computer, a video camera, a goggle-type display, a digital camera, a player using a recording medium, a mobile computer, and a projector.
- 11. A semiconductor device including a circuit which is constituted by a thin film transistor having a semiconductor film as a channel formation region, wherein:
- a carbon concentration and a nitrogen concentration are 5 x  $10^{18}$  atoms/cm<sup>3</sup> or less, and an oxygen concentration is 1.5 x  $10^{19}$  atoms/cm<sup>3</sup> or less;

a main orientation plane is a {110} plane;

an absolute value of a rotation angle made by equivalent axes between adjacent crystal grains or by axes in rotation relation of 70.5° with respect to the equivalent axes is within 4°.

- 12. A semiconductor device according to claim 11, wherein the crystalline semiconductor film is a single crystal or substantially a single crystal.
- 13. A semiconductor device according to claim 11, wherein the crystalline semiconductor film comprises  $Si_xGe_{(1-x)}$  (0<x<1).
- 14. A semiconductor device according to claim 11, wherein the semiconductor device is at least one of a liquid crystal display device and an EL display device.
- 15. A semiconductor device according to claim 11, wherein the semiconductor device is at least one selected from the group consisting of a personal computer, a video camera, a goggle-type display, a digital camera, a player using a recording medium, a mobile computer, and a projector.
- 16. A semiconductor device including a circuit which is constituted by a thin film transistor having a semiconductor film as a channel formation region, wherein:
- a carbon concentration and a nitrogen concentration are 1 x  $10^{18}$  atoms/cm<sup>3</sup> or less, and an oxygen concentration is 5 x  $10^{18}$  atoms/cm<sup>3</sup> or less;

a main orientation plane is a {110} plane;

an absolute value of a rotation angle made by equivalent axes between adjacent crystal grains or by axes in rotation relation of 70.5° with respect to the equivalent axes is within 4°.

- 17. A semiconductor device according to claim 16, wherein the crystalline semiconductor film is a single crystal or substantially a single crystal.
- 18. A semiconductor device according to claim 16, wherein the crystalline semiconductor film comprises  $Si_xGe_{(1-x)}$  (0<x<1).

- 19. A semiconductor device according to claim 16, wherein the semiconductor device is at least one of a liquid crystal display device and an EL display device.
- 20. A semiconductor device according to claim 16, wherein the semiconductor device is at least one selected from the group consisting of a personal computer, a video camera, a goggle-type display, a digital camera, a player using a recording medium, a mobile computer, and a projector.